

ABSTRACT OF THE DISCLOSURE

A coating apparatus 1a for forming a coating film on a coated surface by raising a coating liquid that is reserved
5 under a substrate 10 by a capillary phenomenon of a substrate processing means 2, bringing the raised coating liquid into contact with the coated surface of the substrate 10 that is directed downward, and then moving relatively the substrate processing means 2 and the substrate 10, comprises a holding
10 means 5a for holding detachably the substrate 10, a chucking means 3 for chucking the substrate 10 from the holding means 5a in a state that the processes surface of the substrate 10 is directed downward, and a moving means 4 for moving relatively the substrate processing means 2 and/or the chucking means
15 3 in a horizontal plane.